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FACSIMILE TRANSMITTAL SHEET

DATE : February 26, 2001
TO : Examiner John S. Chu
COMPANY : U.S. Patent and Trademark Office
FAX NO. : 703-872-9367
FROM : Michael I. Markowitz, Esq.

Total Number of Pages including cover 4

Re: U.S. Patent Application No.: 09/036,219
**CHEMICALLY AMPLIFIED RESIST LARGE IN
TRANSPARENCY AND SENSITIVITY TO EXPOSURE...**
Our Reference No.:NEKW 14.868

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enclosed check, may be charged on Deposit Acct. No. 08-
1634.

Attorney Docket No.: NEKW14.868**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Inventor: KAICHIRO NAKANO, ET AL.

Serial No.: 09/036,219

Filed: March 6, 1998

Title: **CHEMICALLY AMPLIFIED RESIST LARGE IN
TRANSPARENCY AND SENSITIVITY TO EXPOSURE
LIGHT LESS THAN 248 NANOMETER WAVELENGTH
AND PROCESS OF FORMING MASK**

Examiner: J. Chu

Group Art Unit: 1752

DATE

Assistant Commissioner for Patents
Washington, D.C. 20231

RESPONSE TO OFFICE ACTION

S I R :

In response to the Office Action mailed on November 29, 2000, the period for
responding thereto having been set to expire on February 28, 2001, please amend the
above-captioned application as follows: